


EE C245 - ME C218 Introduction to MEMS Design Fall 2011

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Lecture Module 1: Admin & Overview

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Instructor: Prof. Clark T.-C. Nguyen

- **Education**: Ph.D., University of California at Berkeley, 1994
- **1995**: joined the faculty of the Dept. of EECS at the University of Michigan
- **2006**: (came back) joined the faculty of the Dept. of EECS at UC Berkeley
- **Research**: exactly the topic of this course, with a heavy emphasis on vibrating RF MEMS
- **Teaching**: (at the UofM) mainly transistor circuit design courses; (UC Berkeley) 140, 143, 243, 245
- **2001**: founded Discera, the first company to commercialize vibrating RF MEMS technology
- **Mid-2002 to 2005**: DARPA MEMS program manager
 - ↳ ran 10 different MEMS-based programs
 - ↳ **topics**: power generation, chip-scale atomic clock, gas analyzers, nuclear power sources, navigation-grade gyros, on-chip cooling, micro environmental control

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Course Overview



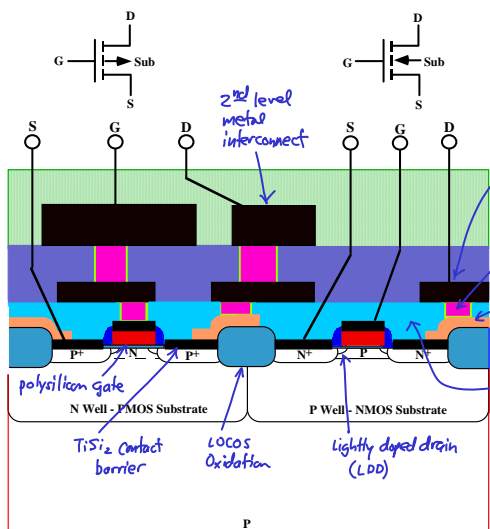
- **Goals of the course:**
 - ↗ Accessible to a broad audience (minimal prerequisites)
 - ↗ Design emphasis
 - Exposure to the techniques useful in analytical design of structures, transducers, and process flows
 - ↗ Perspective on MEMS research and commercialization circa 2010
- **Related courses at UC Berkeley:**
 - ↗ EE 143: Microfabrication Technology
 - ↗ EE 147: Introduction to MEMS
 - ↗ ME 119: Introduction to MEMS (mainly fabrication)
 - ↗ BioEng 121: Introduction to Micro and Nano Biotechnology and BioMEMS
 - ↗ ME C219 - EE C246: MEMS Design
- **Assumed background for EE C245:** graduate standing in engineering or physical/bio sciences

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What Should You Know?



Typical mid-2000's CMOS Process (good down to ~0.25µm)



You should either already know or be able to learn independently & very quickly:

- ① How to deposit or grow those different layers.
- ② How to pattern or otherwise form the shapes of the layers shown.
- ③ What determines the order by which the different layers are formed, e.g., temperature limits, topography limits, etc...

We will review these things, but we will do this very fast!

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What Should You Know?

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Basic Claf. Analysis & Design Using Op Amps

Ex.

$R_f \parallel \frac{1}{sC_f} = \frac{R_f}{1 + sR_fC_f}$

Find the transfer function $\frac{V_o}{V_i}(s)$.

Ideal Op Amp Rules: (Apply when there's neg. FB)

- ① $v_i = v_-$
- ② $R_i = \infty$ (infinite input resistance)

Virtual Ground

$$i_i = \frac{V_i}{R_i}$$

$$V_o = -i_i \left(R_f \parallel \frac{1}{sC_f} \right) = -\frac{V_i}{R_i} \left(R_f \parallel \frac{1}{sC_f} \right) \Rightarrow \frac{V_o}{V_i}(s) = -\frac{R_f}{R_i} \frac{1}{1 + sR_fC_f} = -\frac{R_f}{R_i} \frac{1}{1 + \frac{s}{\omega_b}} = \frac{V_o}{V_i}(s)$$

$$\omega_b = \frac{1}{R_fC_f}$$

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Course Overview

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- The mechanics of the course are summarized in the course handouts, given out in lecture today
 - ↪ Course Information Sheet
 - Course description
 - Course mechanics
 - Textbooks
 - Grading policy
 - ↪ Syllabus
 - Lecture by lecture timeline w/ associated reading sections
 - Midterm Exam: tentatively set for Thursday, Oct. 28
 - Final Exam: Friday, Dec. 17, 7-10 p.m.
 - Change this Final Exam time?
 - Project due date TBD (but near semester's end)

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Lecture Outline

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- Reading: Senturia, Chapter 1
- Lecture Topics:
 - ↳ Definitions for MEMS
 - ↳ MEMS roadmap
 - ↳ Benefits of Miniaturization

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MEMS: Micro Electro Mechanical System

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- A device constructed using micromachining (MEMS) tech.
- A micro-scale or smaller device/system that operates mainly via a mechanical or electromechanical means
- At least some of the signals flowing through a MEMS device are best described in terms of mechanical variables, e.g., displacement, velocity, acceleration, temperature, flow

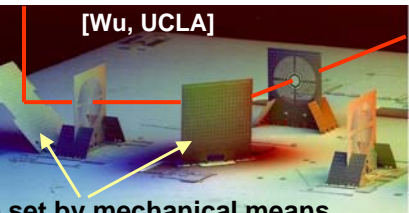
Input:
voltage, current
acceleration, velocity
light, heat ...

MEMS

Output:
voltage, current
acceleration, velocity
light, heat, ...

Transducer to Convert **Control** to a **Mechanical Variable** (e.g., displacement, velocity, stress, heat, ...)

Control:
voltage, current
acceleration
velocity
light, heat, ...



[Wu, UCLA]


Angle set by mechanical means to control the path of light

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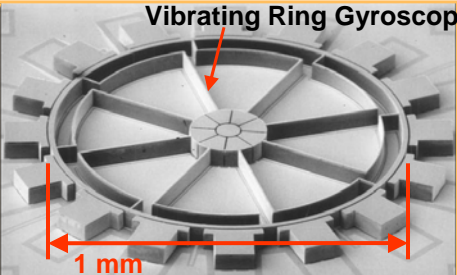
Other Common Attributes of MEMS

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- Feature sizes measured in microns or less

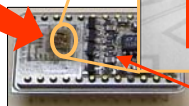


80 mm
Gimbaled, Spinning
Macro-Gyroscope



[Najafi, Michigan]
Micromechanical
Vibrating Ring Gyroscope

1 mm



MEMS Technology
(for 80X size Reduction)

Signal Conditioning Circuits

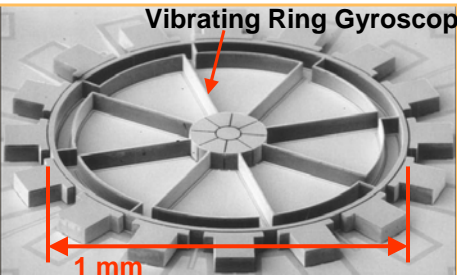
- Merges computation with sensing and actuation to change the way we **perceive** and **control** the physical world
- Planar lithographic technology often used for fabrication
 - ↳ can use fab equipment identical to those needed for IC's
 - ↳ however, some fabrication steps transcend those of conventional IC processing

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Bulk Micromachining and Bonding

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- Use the wafer itself as the structural material
- Adv: very large aspect ratios, thick structures
- Example: deep etching and wafer bonding



Micromechanical
Vibrating Ring Gyroscope

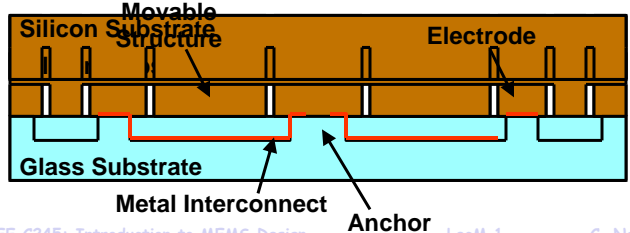
1 mm

[Najafi, Michigan]



[Pisano, UC Berkeley]

Microrotor
(for a microengine)



Movable Structure
Silicon Substrate
Electrode
Glass Substrate
Metal Interconnect
Anchor

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Surface Micromachining

The diagram illustrates the surface micromachining process in two stages. In the top stage, a silicon substrate with p-wells contains a sacrificial oxide layer, a structural material layer (e.g., polysilicon, nickel, etc.), and a release etch barrier. A hydrofluoric acid release solution is applied to the sacrificial oxide. In the bottom stage, the sacrificial oxide has been removed, leaving a free-standing resonator beam on the silicon substrate.

- Fabrication steps compatible with planar IC processing

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Single-Chip Ckt/MEMS Integration

The micrograph shows a single-chip integrated circuit/MEMS device. Labels include: Sustaining Amplifier, Input, Comb. Transducer, Shuttle, Mass, Folded-Beam Suspension, Anchors, and V_p . A scale bar indicates 300 μm . An inset shows an oscilloscope output waveform with the following data:

CH1	P-P	=	324mV
CH1	FRE	=	21.52
CH1	PER	=	61.22
CH1	PER	=	18.16

Oscilloscope Output Waveform

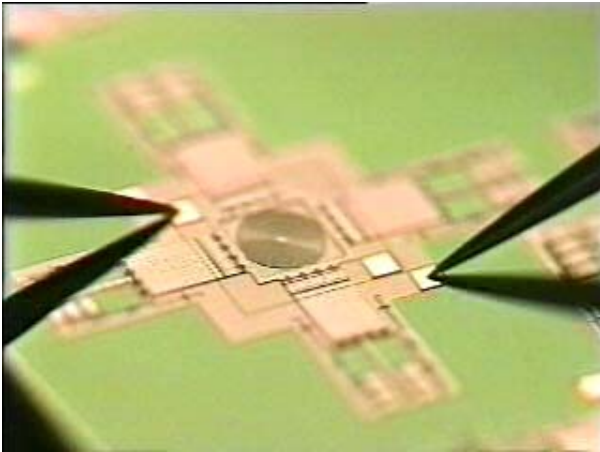
[Nguyen, Howe 1993]

- Completely monolithic, low phase noise, high-Q oscillator (effectively, an integrated crystal oscillator)
- To allow the use of $>600^\circ\text{C}$ processing temperatures, tungsten (instead of aluminum) is used for metallization

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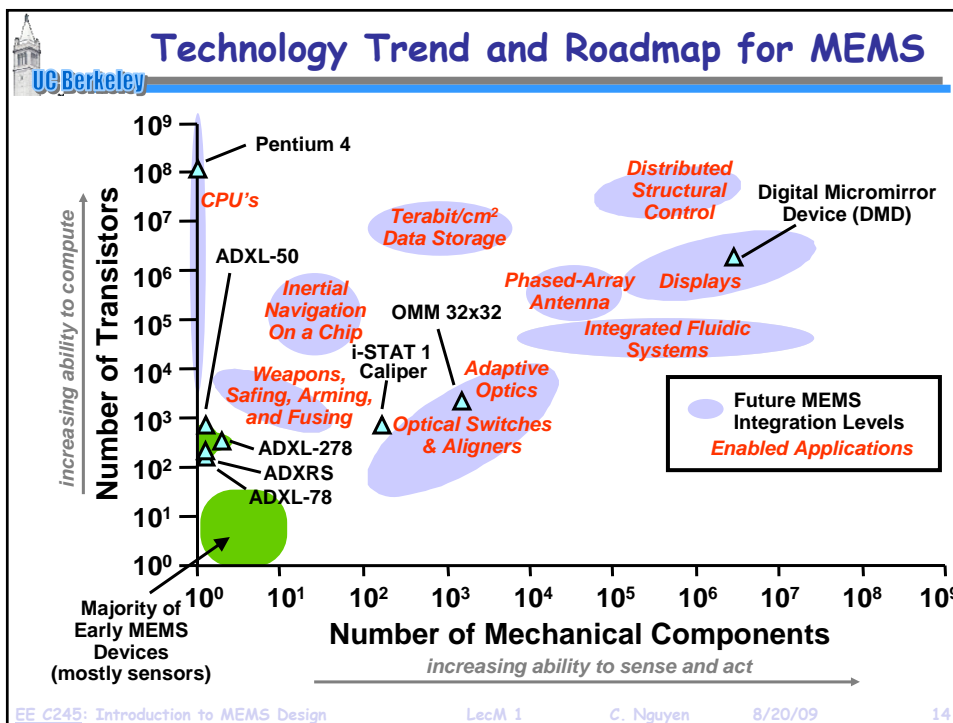
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3D Direct-Assembled Tunable L



[Ming Wu, UCLA]

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Example: Micromechanical Accelerometer

The MEMS Advantage:

- >30X size reduction
- accelerometer mechanism
- allows integration

Basic Operation Principle

$x \propto F_i = ma$

Tiny mass means small output \Rightarrow need integrated transistor circuits to compensate

Analog Devices ADXL 78

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Technology for MEMS

Adv.: small size

Adv.: faster switching, low loss, larger networks

Adv.: low loss, fast switching, high fill factor

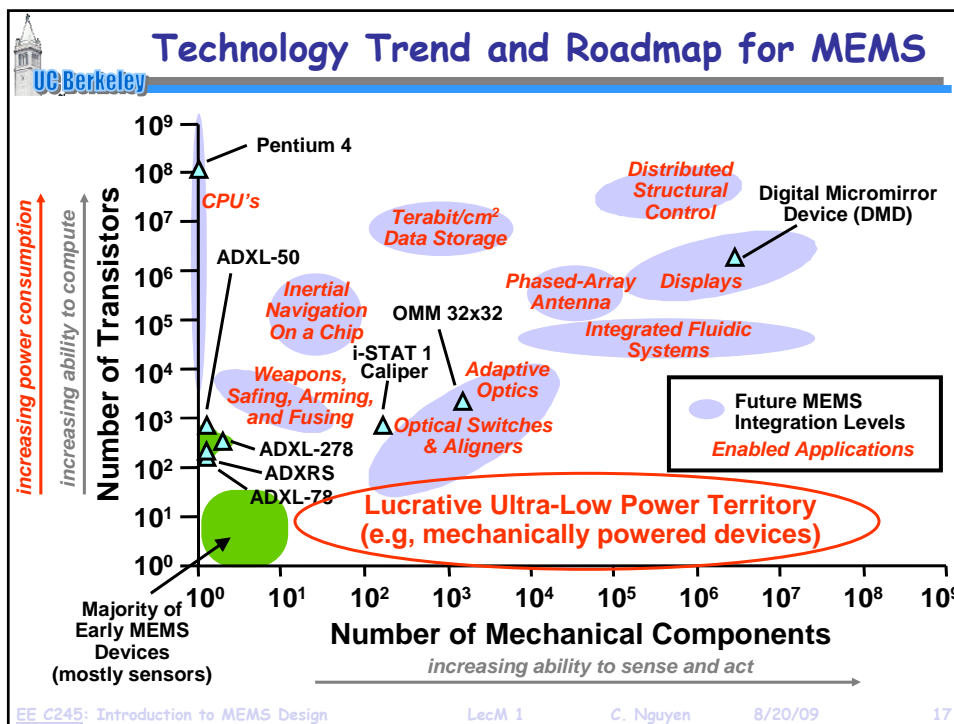
Adv.: small size, small sample, fast analysis speed

Number of Mechanical Components: $10^2, 10^3, 10^4, 10^5$

increasing ability to sense and act

Devices shown: Analog Devices ADXR Integrated Gyroscope, OMM 8x8 Optical Cross-Connect Switch, Digital Micromirror Device (DMD), i-STAT 1 Caliper, Adaptive Optics, Optical Switches & Aligners, Caliper Microfluidic Chip, TI Digital Micromirror Device, Future MEMS.

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Benefits of Size Reduction: MEMS

- Benefits of size reduction clear for IC's in elect. domain
 ↺ size reduction ⇔ speed, low power, complexity, economy
- MEMS: enables a similar concept, but ...
MEMS extends the benefits of size reduction beyond the electrical domain

↓

Performance enhancements for application domains beyond those satisfied by electronics in the same general categories

- Speed → Frequency ↑ , Thermal Time Const. ↓
- Power Consumption → Actuation Energy ↓ , Heating Power ↓
- Complexity → Integration Density ↑ , Functionality ↑
- Economy → Batch Fab. Pot. ↑ (esp. for packaging)
- Robustness → g-Force Resilience ↑

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